

POWERED BY **Dialog****Electrolytic removal of oxide scale from copper - in aq. sulphate bathm using the copper as anode then as cathode****Patent Assignee: FURUKAWA ELECTRIC CO LTD****Patent Family**

Patent Number	Kind	Date	Application Number	Kind	Date	Week	Type
JP 75005988	B	19750310				197514	B

Priority Applications (Number Kind Date): JP 7024255 A (19700323)**Abstract:**

JP 75005988 B

A Cu pickling process comprises (a) passing D.C. at current density of 1-80 A/cm² through an aq. soln. contg. 20-300 g/l H₂SO₄ and 15-70 g/l Cu ions (as CuSO₄), using the Cu matl. to be treated as anode, the oxide layer being removed and Cu being deposited on the cathode and (b) using the treated Cu matl. as cathode (and an inactive matl. as anode) in the soln. used in (a), passing D.C. at current density ≤ 40 A/dm² through the soln.

The H₂SO₄ consumed in (a) regenerated and simultaneously Cu is deposited on the matl. being treated. The process can be used to treat Cu cables or springs. The oxide scale is of thickness 4 μ and comprises 90 wt.% CuO and 10 wt.% Cu₂O.

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